

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings of claims in the application:

Claims 1-2 (Canceled).

Claim 3 (Currently Amended): ~~The~~ A halogenoacetoxyadamantane derivative as described in claim 1 or 2, wherein it is ~~2-halogenoacetoxyadamantane, 2-alkyl-2-halogenoacetoxyadamantane, 1-halogenoacetoxyadamantane, 1-halogenoacetoxy-3-hydroxyadamantane, 1,3-bis(halogenoacetoxy)adamantane or which is 1-~~ halogenoacetoxyperfluoroadamantane.

Claim 4 (Currently Amended): ~~The~~ A halogenoacetoxyadamantane derivative as described in claim 3, wherein it is which is 2-alkyl-2-halogenoacetoxyadamantane.

Claim 5 (Currently Amended): ~~The~~ A halogenoacetoxyadamantane derivative as described in claim 3, wherein it is which is 1-halogenoacetoxy-3-hydroxyadamantane.

Claim 6 (Currently Amended): A process for producing a halogenoacetoxyadamantane derivative, comprising:

~~the step of~~ reacting a hydroxyl group of an adamantane skeleton directly with halogenoacetic halide or reacting ~~the above~~ said hydroxyl group with a lithiation agent to ~~derive it into~~ obtain a lithiumoxy group and then reacting halogenoacetic halide therewith to introduce a halogenoacetoxy group;

wherein said halogenoacetoxyadamantane derivative is 2-alkyl-2-halogenoacetoxyadamantane, 1-halogenoacetoxy-3-hydroxyadamantane or 1-halogenoacetoxyperfluoroadamantane.

Claim 7 (New): The process of Claim 6, wherein said lithiating agent is lithium metal, n-butyllithium, sec-butyllithium or tert-butyllithium.

Claim 8 (New): A photoresist composition, comprising:
the halogenoacetoxyadamantane derivative of Claim 3.

Claim 9 (New): A photoresist composition, comprising:
the halogenoacetoxyadamantane derivative of Claim 4.

Claim 10 (New): A photoresist composition, comprising:
the halogenoacetoxyadamantane derivative of Claim 5.

Claim 11 (New): A dry-etching resistance improving agent, comprising:
the halogenoacetoxyadamantane derivative of Claim 3.

Claim 12 (New): A dry-etching resistance improving agent, comprising:
the halogenoacetoxyadamantane derivative of Claim 4.

Claim 13 (New): A dry-etching resistance improving agent, comprising:
the halogenoacetoxyadamantane derivative of Claim 5.

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BASIS FOR THE AMENDMENT

Claims 1 and 2 have been canceled.

Claims 3, 4, 5 and 6 have been amended as supported by the original claims and the specification.

New Claim 7 is supported by the paragraph bringing pages 9 and 10 of the specification.

New Claims 8-13 are supported by the paragraph bridging pages 15 and 16.

No new matter is believed to have been added by entry of this amendment. Entry and favorable reconsideration are respectfully requested.

Upon entry of this amendment Claims 3-13 will now be active in this application.